

**Notice of Allowability**

Application No.

10/718,102

Examiner

Thanhha Pham

Applicant(s)

RAVI, KRAMADHATI V.

Art Unit

2813

**-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--**

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to 03/24/2006.
2. ☒ The allowed claim(s) is/are 1,6-8,23-28 and 33-35.
3. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some\* c) ☐ None of the:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).
- \* Certified copies not received: \_\_\_\_\_.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  
**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
- (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
- 1) ☐ hereto or 2) ☐ to Paper No./Mail Date \_\_\_\_\_.
- (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date \_\_\_\_\_.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

**Attachment(s)**

1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No./Mail Date \_\_\_\_\_
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material
5. ☐ Notice of Informal Patent Application (PTO-152)
6. ☒ Interview Summary (PTO-413), Paper No./Mail Date 04/14/2006.
7. ☒ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other \_\_\_\_\_.

  
Thanhha Pham

### EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Glen Choi on 04/14/2006.

The application has been amended as follows:

- In claim 1,
  - line 2, before "coating" insert -- first --
  - line 3, after "wafer" insert -- with the first coating --
  - line 4, before "coating" insert -- first --
  - line 4, change "of" to -- over --
  - line 5, change "a layer of coating" to -- a layer of a second coating --
  - line 5, change "each coating" to -- each of the first coating and the second coating --
- In claim 7,
  - line 3, change "the coating of the wafer" to -- the first coating over the wafer --
- In claim 8,
  - line 2, change "a" to -- the --
- In claim 23,

line 2, change "providing a coating" to -- providing the first coating --

- In claim 24,

line 3, before "coating" insert -- first --

line 5, before "coating" insert -- first --

- In claim 25,

line 2, change "the coating of" to -- the first coating over --

- In claim 26,

line 2, before "coating" insert -- first --

line 3, change "layer of coating" to -- layer of a second coating --

line 3, change "each coating" to -- each of the first coating and the second coating --

line 6, after "wafer" insert -- with the second coating --

- In claim 27,

line 3, before "coating" insert -- first --

line 5, before "coating" insert -- first --

- In claim 28,

line 3, before "coating" insert -- first --

- In claim 34,

line 3, before "coating" insert -- second --

- In claim 35,

line 2, change "a" to -- the --

***Allowable Subject Matter***

2. Claims 1, 6-8, 23-28 and 33-35 allowed.

3. The following is an examiner's statement of reasons for allowance: Present application includes 2 independent claims. Independent claim 1 recites a method comprising: providing a first coating over a wafer; testing a semiconductor tool using the coated wafer with the first coating; and replacing at least a portion of the first coating over the wafer with a layer of a second coating wherein each of the first coating and the second coating comprises at least one characteristic of a single crystal structure. Independent claim 26 recites a method comprising: replacing at least a portion of a first coating of a wafer with a layer of a second coating wherein each of the first coating and the second coating has at least one characteristic of a single structure; and testing at least one characteristic of a semiconductor tool using the coated wafer with the second coating. The present invention claims method testing a semiconductor tool using the coated wafer with the first coating (independent claim 1) or the second coating (independent claim 26) wherein each of the first coating and the second coating comprising at least one characteristic of a single crystal structure. Rojhtantalab (US 6,761,625) appears to be closest prior that uses a wafer itself comprising a single crystal structure to test a semiconductor tool and polishing the wafer to remove particles from the wafer surface (not the coated wafer with the first coating or second coating wherein each of the first coating and the second coating comprising at least one characteristic of the single crystal structure ). Therefore, Recorded Prior Arts including Rojhtantalab fail to disclose or suggest using the coated wafer with the first coating or

second coating wherein each of the first coating and the second coating comprising at least one characteristic of the single crystal structure to test the semiconductor tool.

Recorded Prior Arts also fail to disclose or suggest the claimed method as cited in claims 1 and 26 comprising replacing at least a portion of the first coating over/of the wafer with a layer of second coating wherein each of the first coating and the second coating comprises/has at least one characteristic of a single crystal structure.

4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanhha Pham whose telephone number is (571) 272-1696. The examiner can normally be reached on Monday and Thursday 9:00AM - 9:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

A handwritten signature in black ink, consisting of several loops and a long horizontal stroke extending to the right.

Thanhha Pham